

Form PTO-1449
(Rev. 8-83)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO:
101328-148APPLICATION NO:
09/512,942

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

APPLICANT:
Theodore H. FedynyshynFILING DATE:
February 25, 2000GROUP ART UNIT:
2852

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE*
	AC	5	6	4	8	1	5	9	07/97	Sato	428	327	
	AD	5	7	5	3	7	2	2	05/98	Itokawa et al.	522	83	

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FOREIGN PATENT DOCUMENTS

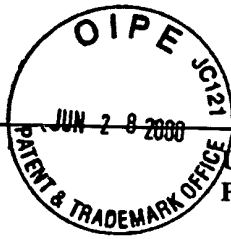
		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
	BC	3	2	3	7	1	1	3	10/91	Japan			abs	
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	BE	0	8	3	6	2	6	5	02/96	Japan				X

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OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

	CI ✓	Pu, J.-L. et al., "Photobinding of Colloidal Particles by Means of Surface Modification. III. Influences of Dispersibility and Photoactivity of Azido Groups on the Colloidal Surface," <i>Journal of Imaging Science</i> , vol. 33, no. 1, 33-35 (January/February 1989);											
	CJ ✓	Vossmeier, T. et al., "Light-Directed Assembly of Nanoparticles," <i>Angew. Chem. Int. Ed. Engl.</i> , vol. 36, no. 10, 1080-3 (1997);											
	CK ✓	Zambounis, J.S. et al., "Latent Pigments Activated by Heat," <i>Nature</i> , vol. 388, 131-2 (July 10, 1997).											
Examiner		Date Considered:											
		*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and considered. Include copy of this form with next communication to applicant.											

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AA	3 8 0 1 3 2 7	04/74	Moreau	96	115R	
AB	4 2 0 2 6 9 7	05/80	Van Goethem et al.	430	306	

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DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
					YES NO
BA 1 0 2 0 4 3 8	01/89	Japan			abst
BB 0 3 2 4 2 7 9	03/91	Japan			X

OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

CA	✓	Bruschi, P. et al., "Gas Sensing with Conducting Polymer Thin Film Resistors Obtained From Commercial Photoresist Patterns," <i>Sens. Microsyst., Proc. Ital. Conf.</i> , Di Natale et al. (Editors), 69-73 (1996);
CB	✓	Crivello, J. and Mao, Z., "Preparation and Cationic Photopolymerization of Organic-Inorganic Hybrid Matrixes," <i>Chem. Mater.</i> , vol. 9, 1562-69 (1997);
CC	✓	Dagani, R., "Putting the 'Nano' into Composites," <i>Chemical</i> , 25-37 (June 7, 1999);
CD	✓	Dumpich, G. et al., "Direct Writing of Metallic Nanostructures by Means of Metal Colloids," <i>Materials Science Forum</i> , vols. 287-8, 413-6 (1998);
CE	✓	Kaplan, L.H. and Zimmerman, S.M., "Enhanced E-Beam Sensitivity of Resist," <i>IBM Technical Disclosure Bulletin</i> , vol. 21, no. 7, p. 2823 (December 1978);
CF		Mucha, et al., "Plasma Etching of Materials Used in Microelectronic Manufacturing," <i>Introduction to Microlithography</i> , L. Thompson et al., (editors), 449-64 (1994);
CG	✓	Pu, Jia-Ling et al., "Photobinding of Colloidal Particles by Means of Surface Modification," <i>Journal of Imaging Science</i> , vol.32, no. 3, 129-34 (May/June 1988);
CH	✓	Pu, Jia-Ling et al., "Photobinding of Colloidal Particles by Means of Surface Modification. II. Surface Azido Density and Dispersibility," <i>Journal of Imaging Science</i> , vol.32, no.6, 232-7 (November/December 1988);
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